

Abstract

SUBSTRATE PROCESSING APPARATUS AND SUBSTRATE PROCESSING SYSTEM

A substrate processing apparatus configured to process a substrate, the substrate processing apparatus including: a processing chamber; and a support member disposed in the processing chamber and having a tray supporting surface for supporting a tray on an upper surface of the support member, in which the tray is formed with a recess accommodating the substrate on an upper surface of the tray, the support member includes a lift pin configured to lift and lower the tray at an upper portion of the support member, the support member is formed with a through-hole into which the lift pin is inserted, and the through-hole is formed at a position where the through-hole does not overlap with the tray in plan view when the tray is disposed on the support member.

Fig. 4